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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1752**

Serial No.: **10/629,806**

Examiner: **LEE, SIN J**

Filed: **July 30, 2003**

Confirmation No.: **9494**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR
FORMING RESIST PATTERN, AND PROCESS FOR MANUFACTURING
SEMICONDUCTOR DEVICE**

Attorney Docket No.: **030923**

Customer Number: **38834**

RESPONSE UNDER 37 CFR §1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 8, 2005

Sir:

This paper is in response to the Office Action dated November 29, 2004.

Remarks begin on page 2 of this paper.